TEL Formula Configuration :

Description: Diffusion（Amorphous Anneal, α-Si）
Manufacturer: TEL
Model: FORMULA
S/W Version 2.0

Configuration:
< Basic Configuration >
Thoroughput: 50 wafers in Batch

Temperature: 850℃

Gas Unit: PH3 1% ,F2, H2, O2 ,

System Controller: WAVES/Model780

Heater: Mid-Temp VCM-50-XXX

Exhaust Controller: CKD VEC

EXH Box: Standard Type (190 cm width)

Dry Pump: Exclude

< Gas Configuration >

Gas Pressure Flow Connection Type

Gas Box

P-N2 0.5MPa 92 L/min ϕ1/4"UJR

1%PH3/He 0.2MPa 5 L/min ϕ1/4"UJR

H2 0.2MPa 5 L/min ϕ1/4"UJR

O2	0.2MPa	5	L/min	ϕ1/4"UJR
F2	0.2MPa	5	L/min	ϕ1/4"UJR

EXH Box

P-N2	-	-	ϕ3/4"SWG
P-N2	-	-	ϕ1/2"SWG
P-N2	-	-	ϕ1/2"SWG

D-N2 - - ϕ3/8"SWG

D-N2 - - ϕ3/8"SWG

D-N2 - - ϕ1/4"SWG

Vacuum 20KPa - ϕ3/8"SWG

RCU

P-N2 0.7MPa 1200 L/Min ϕ3/4"SWG

D-N2 0.7MPa - ϕ1/4"SWG

P-N2 - - ϕ3/4"SWG

P-N2 - - ϕ1/2"SWG

P-N2 - - ϕ1/2"SWG

D-N2 - - ϕ3/8"SWG

D-N2 - - ϕ3/8"SWG

D-N2 - - ϕ1/4"SWG

Pump

D-N2 0.7MPa - ϕ1/4"SWG

D-N2 0.7MPa 110 L/min ϕ1/2"SWG